

REMARKS


Reconsideration is requested on the basis previously requested and, further, particularly with respect to claim 28.

Claim 28 calls for lowering the glass transition temperature of the photoresist "during the develop rinse." The office action does not even talk about the develop rinse and, moreover, expressly states on page 7, first full paragraph, that it would have been obvious to prepare the material of Hallock, choosing to dry the pattern's substrate post-development of Verhaverbeke with reasonable expectation of achieving the pattern. But, even if all of this were true, there is no suggestion of lowering the glass transition temperature during the develop rinse in particular. In fact, the develop rinse is not even discussed, much less the idea of lowering the glass transition temperature of the photoresist during that develop rinse.

Therefore, at least reconsideration of the rejection of claim 28 would be appropriate.

Respectfully submitted,

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Timothy N. Trop, Reg. No. 28,994  
TROP, PRUNER & HU, P.C.  
1616 South Voss Road, Suite 750  
Houston, TX 77057-2631  
713/468-8880 [Phone]  
713/468-8883 [Fax]

Attorneys for Intel Corporation